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Serial Number: 10/808827


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2.) See attached EAST Inventor Search
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PALM INTRANET

Inventor Information for 10/808827

Inventor Name	City	State/Country
PRASAD, ABANESHWAR	NAPERVILLE	ILLINOIS

Appln. Info	Contents	Petition Info	Atty/Agent Info	Continuity Data	Foreign Data
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US 20030220061 A	US-PGPUB	200311	Microporous polishing pads	451/52		Prasad, Abaneshwar
US 20040082276 A	US-PGPUB	200404	Transparent microporous material CMP	451/41		Prasad, Abaneshwar
US 20040157533 A	US-PGPUB	200408	CMP pad with composite trans window	451/41		Prasad, Abaneshwar
US 20040171338 A	US-PGPUB	200409	Microporous polishing pads	451/52	451/52	Prasad, Abaneshwar
US 20040171339 A	US-PGPUB	200409	Microporous polishing pads	451/52		Prasad, Abaneshwar
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US 20040258882 A	US-PGPUB	200412	Polishing pad with oriented por structure	428/14	428/13	Prasad, Abaneshwar
US 20040259484 A	US-PGPUB	200412	Multi-layer polishing pad mate CMP	451/28		Prasad, Abaneshwar e
US 20050098540 A	US-PGPUB	200505	Polishing pad comprising biode polymer	216/88		Prasad, Abaneshwar
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US 20050153634 A	US-PGPUB	200507	Negative poisson's ratio materi containing CMP polishing pad	451/41	451/52	Prasad, Abaneshwar e
US 20050197050 A	US-PGPUB	200509	Multi-layer polishing pad mate CMP	451/41		Prasad, Abaneshwar e
US 20050211376 A	US-PGPUB	200509	Polishing pad comprising hydro region and endpoint detection p	156/34	216/89	Prasad, Abaneshwar
US 20050215177 A	US-PGPUB	200509	CMC porous pad with compon pores	451/5	451/41	Prasad, Abaneshwar
US 20050215179 A	US-PGPUB	200509	Low surface energy CMP pad	451/8	451/41 451/52	Prasad, Abaneshwar
US 20050276967 A	US-PGPUB	200512	Surface textured microporous p pads	428/31	428/15 428/15 428/16 428/31	Prasad, Abaneshwar
US 20050277371 A	US-PGPUB	200512	Transparent microporous materi CMP	451/28		Prasad, Abaneshwar
US 20060046622 A	US-PGPUB	200603	Polishing pad with microporous	451/41	451/53	Prasad; Abaneshwar
US 6884156 B2	USPAT	200504	Multi-layer polishing pad mate CMP	451/53	451/52 451/53	Prasad; Abaneshwar e
US 6896593 B2	USPAT	200505	Microporous polishing pads	451/41	451/52 451/53	Prasad; Abaneshwar
US 6899598 B2	USPAT	200505	Microporous polishing pads	451/41	451/52 451/53	Prasad; Abaneshwar
US 6913517 B2	USPAT	200507	Microporous polishing pads	451/41	451/52 451/53	Prasad; Abaneshwar
US 6935931 B2	USPAT	200508	Microporous polishing pads	451/41	451/52 451/53	Prasad; Abaneshwar
US 6960120 B2	USPAT	200511	CMP pad with composite trans window	451/41	451/28 451/28	Prasad; Abaneshwar

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US 6998166 B2	USPAT	200602	Polishing pad with oriented por structure	428/14	428/15 428/22 428/30 428/33 428/42 428/42 451/52 451/53 51/298	Prasad; Abaneshwar